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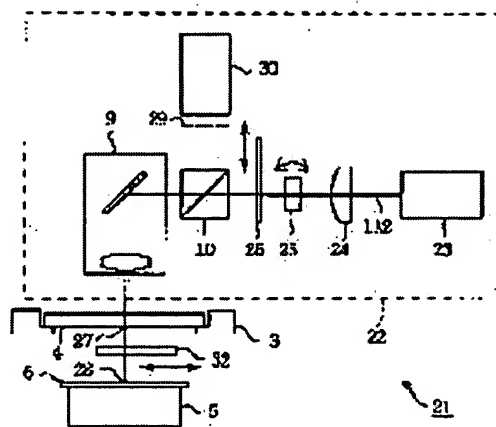
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## (54) ALIGNMENT METHOD FOR PROXIMITY ALIGNER

### (57)Abstract:

**PURPOSE:** To realize highly accurate alignment between a mask and a photosensitive substrate while setting a large interval between them by determining the relative positions first and second alignment marks with respect to a luminous flux individually.

**CONSTITUTION:** An automatic halving 25 is rotated to scan the vicinity of an alignment mark 27 on a mask 4 by means of a long beam. When the laser light LA2 aligns with the alignment mark 27, a detector 30 detects a diffracted light having highest intensity and the relative position between the laser light LA2 and the mask 4 is determined. A beam length switching shutter 26 is then shifted to form a short beam which is projected onto the vicinity of an alignment mark 28 on a photosensitive substrate 6 thus aligning the laser light LA2 with the alignment mark 28. When the relative position of the alignment marks 27, 28 is determined sequentially with respect to the laser light LA2, the mask 4 is aligned accurately with the photosensitive substrate 6 through the laser light LA2.



## LEGAL STATUS

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